

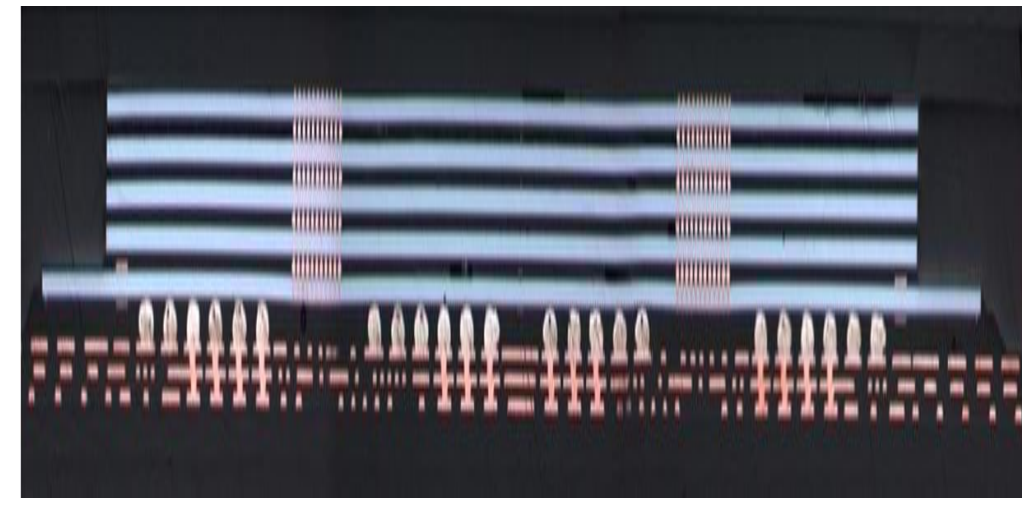
Feasibility studies and optimization of μ -channel cooling for 3D IC

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Motivation

- 3-Dimensional Stacking** is one of the key advanced packaging approaches
 - This work focuses on **3D IC**
- Low power 3D stacks** for memory applications
 - Successfully deployed in last decade (HBM, HMC, NAND) supported by TSVs
- High-power 3D stacks** with heterogeneous integration are being developed:
 - High temperatures, thermal gradients and cross-talk lead to reliability issues
 - Internal layers require direct cooling path
- Micro(μ)-channel cooling** with water is the primary candidate:

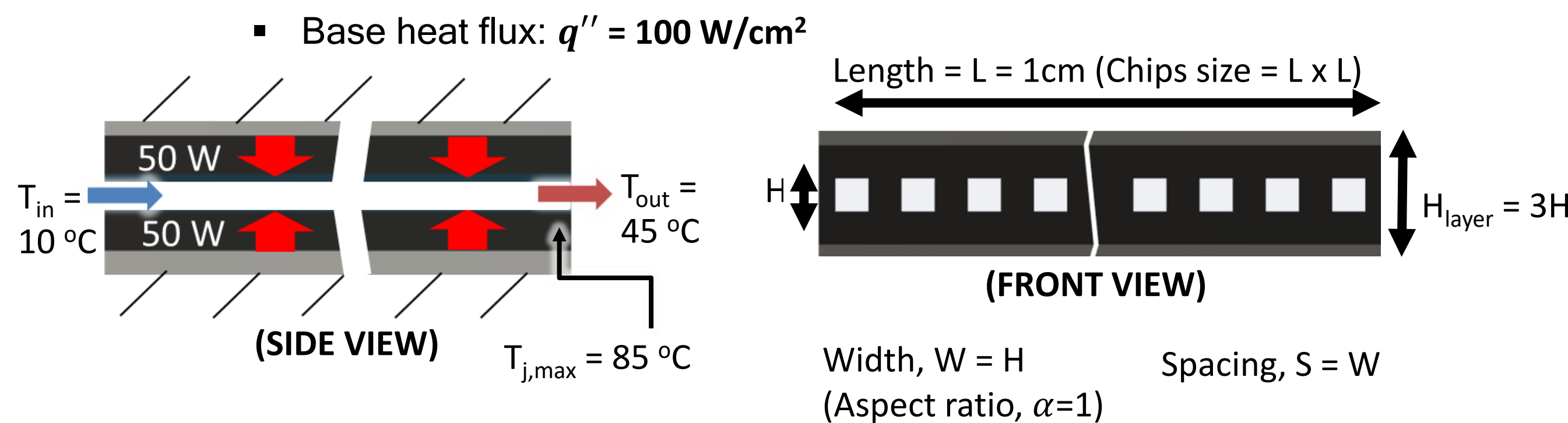
Q. What is the minimum μ -channel height (H) and layer height (H_{layer}) needed to support it?



HMC stack (Courtesy: Micron/IBM)

Simplified μ -channel analysis with Jupyter

- Single adiabatic layer:** All heat produced within the layer needs to be taken out by the μ -channel

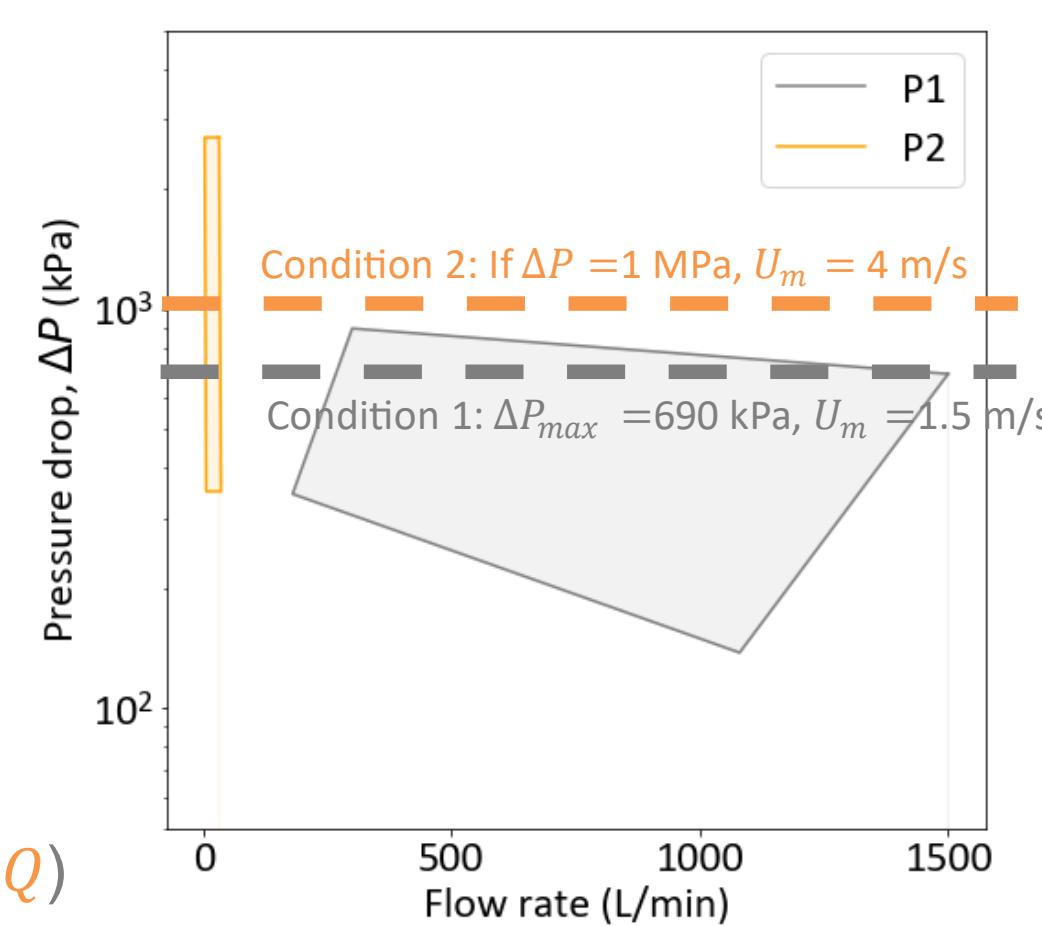


Flow considerations

- Fully Developed laminar flow:**
 - Caloric limit (sensible heating):** $Q_{min} = \frac{q'' L^2}{\rho C_p (T_{out} - T_{in})}$; $U_m = \frac{Q_{min}}{WH}$
 - Pressure drop:** $\Delta P = 2 * (f Re(\alpha)) * \frac{\mu u_m L}{D_h^2} + K(\alpha) * \frac{\rho u_m^2}{2} + 40 \text{ kPa}$
 - Heat Transfer limit:** $q''_{max} = \bar{h} A_s (\bar{T}_j - \bar{T}_m) * \frac{N}{L^2} > q'' (100 \text{ W/cm}^2)$

Operational considerations

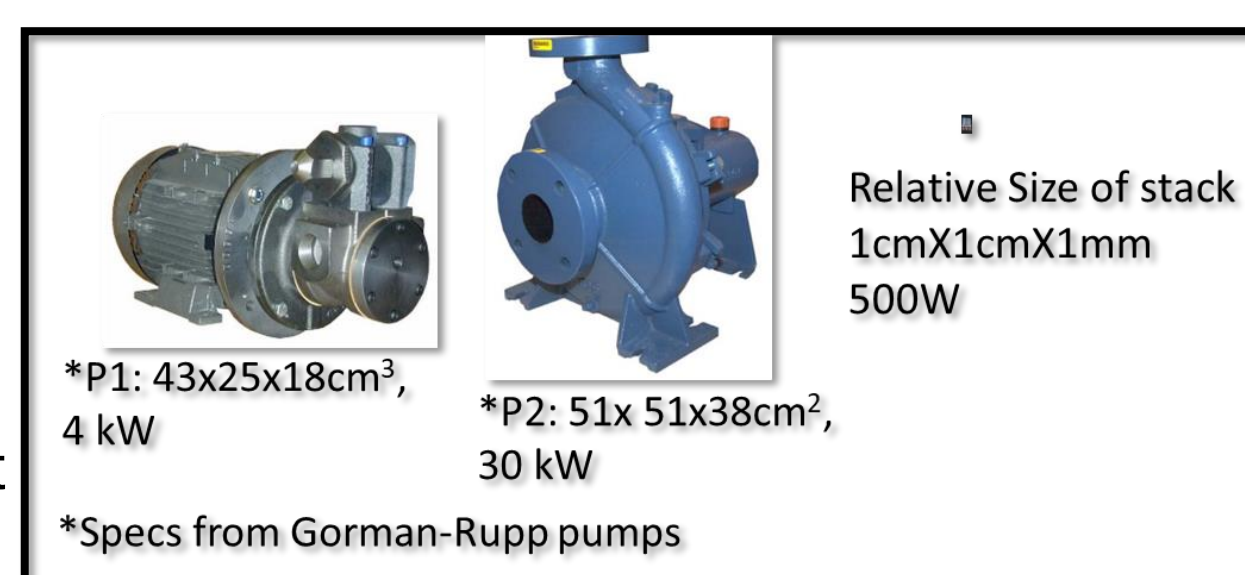
- Operational limits:** Temperature, pressure drop and velocity limits
 - Examples:
 - Condition 1 (ASHRAE W4#)
 - Condition 2 (Hypothetical)
- Pump curves:** Decides number of pumps and pumping power necessary
 - P1: Centrifugal (Low ΔP , high Q)
 - P2: Positive displacement (High ΔP , low Q)



#Thermal Guidelines for Data Processing Environments (3rd Edition), Table 3.1

Electrical and packaging co-design constraints

- Fabrication limits:**
 - Examples - $H < H_{max}$, $\alpha < 10$
- 3D stack constraints:**
 - Form factor ($< 1 \text{ mm}$ high)
 - TSV aspect ratio and placement
 - Coupling of μ -channel to pump
 - Reliability and cost

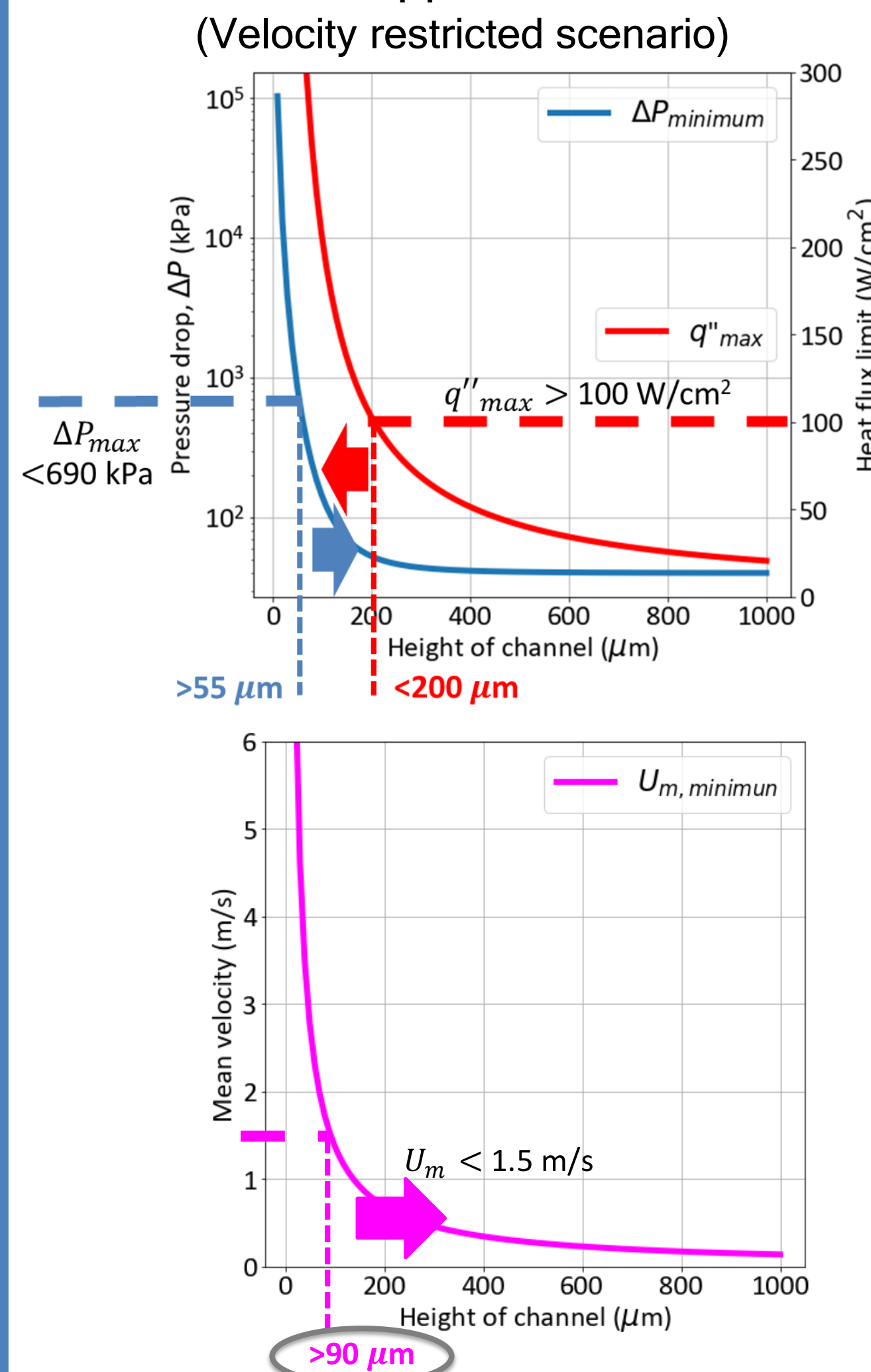


*Specs from Gorman-Rupp pumps

Optimization under sample conditions

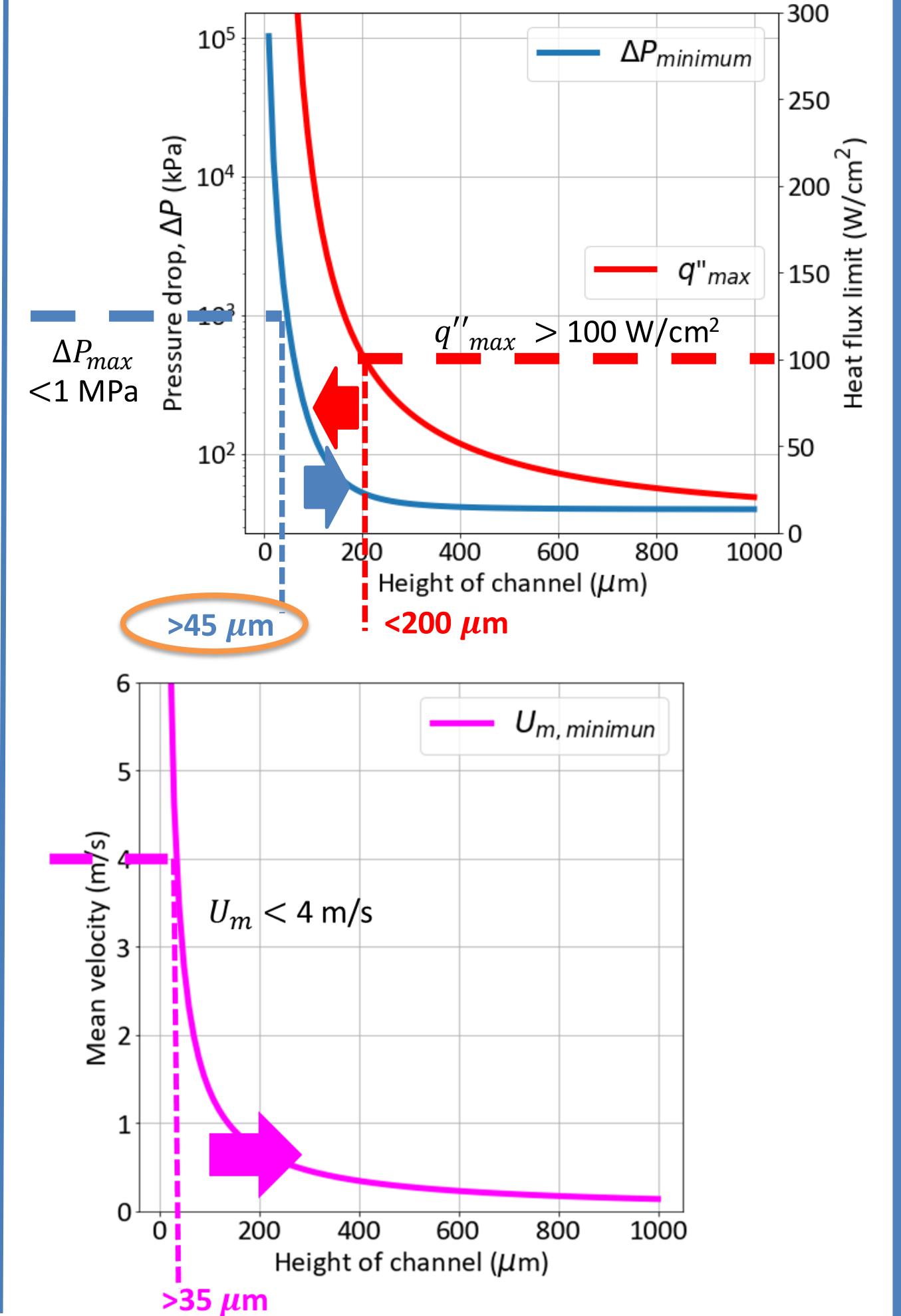
Operating condition 1

- Application of flow limits to identify allowable heights

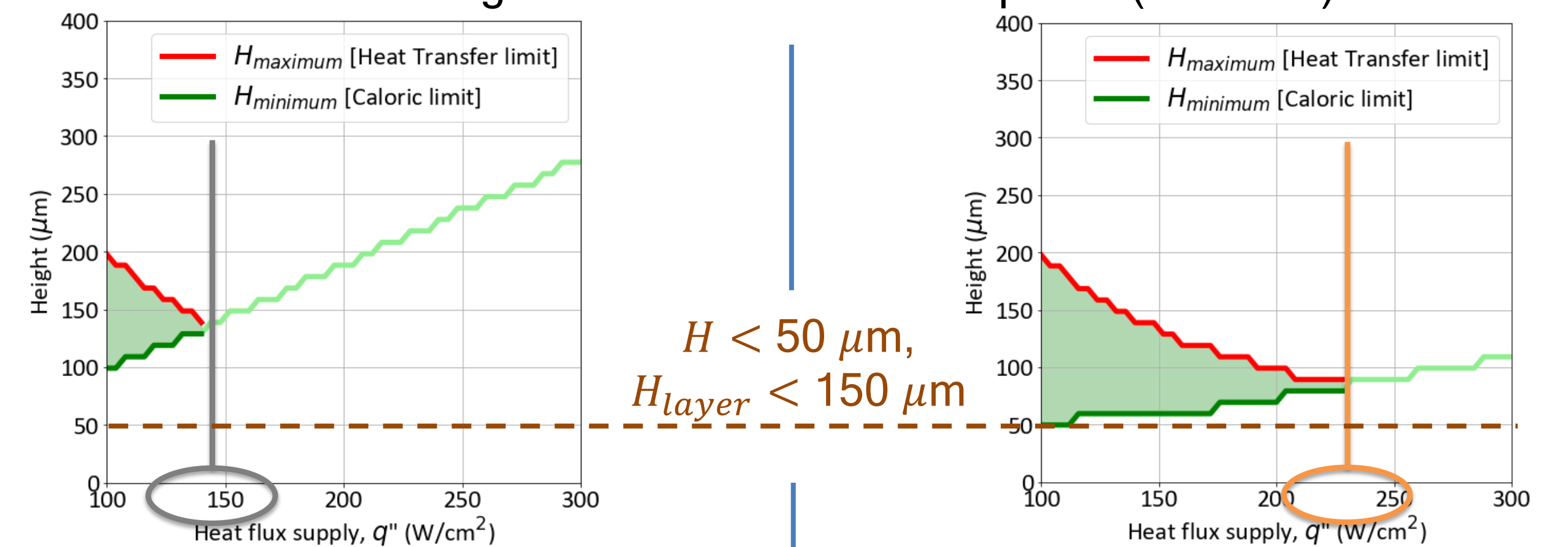


Operating condition 2

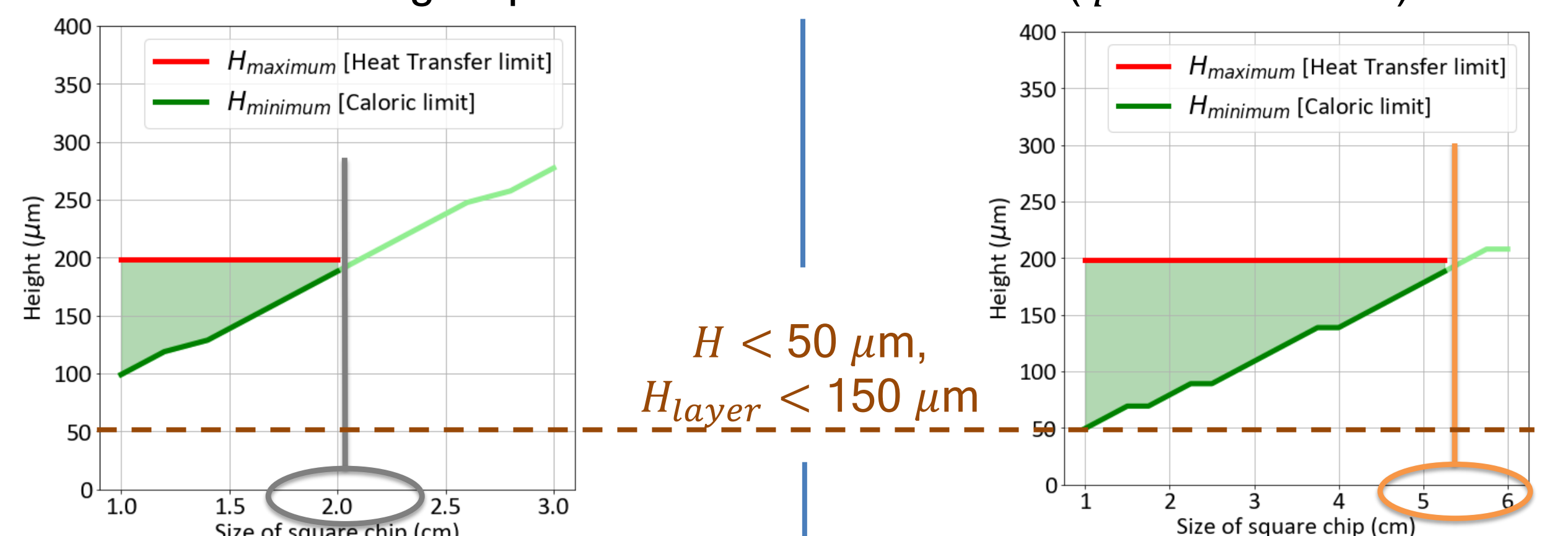
- (Pressure drop restricted scenario)



- Increasing heat flux at constant chip size ($L = 1 \text{ cm}$)



- Increasing chip size at constant heat flux ($q'' = 100 \text{ W/cm}^2$)



Conclusions

- Micro(μ)-channel cooling for 3D IC** presents a formidable challenge when all dies are high-power ($> 100 \text{ W/cm}^2$)
 - Key limitation is the channel height required to sustain high flow rates with practical pressure drops ($< 1 \text{ MPa}$)
 - Significant temperature gradient within 1 cm die length
- Experimental studies needed for reliability constraints for high-pressure flow within stack
- If the maximum layer height is restricted to $150 \mu m$:
 - No operating points for heat flux, $q'' > 100 \text{ W/cm}^2$

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